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(12) **United States Design Patent**
Kimura

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(54) **WAFER HOLDER FOR ION IMPLANTATION**

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(**) Term: **14 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (10) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/182; 118/500, 728, 729; 414/217,
414/222.01, 416.03, 935, 936, 937, 938,
414/939, 940, 941; 156/345.1, 345.52,
156/345.53

See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a wafer holder for ion implantation, as shown and described.

DESCRIPTION

FIG. 1 is a front view of a wafer holder for ion implantation showing my new design;
FIG. 2 is a rear view thereof;
FIG. 3 is a top plan view thereof;
FIG. 4 is a bottom plan view thereof;
FIG. 5 is a right side view thereof;
FIG. 6 is a left side view thereof;
FIG. 7 is a perspective view thereof; and,
FIG. 8 is an enlarged cross sectional view taken along line 8-8 of FIG. 3 thereof.

The broken lines shown in the drawings represent portions of the wafer holder for ion implantation that form no part of the claimed design.

1 Claim, 8 Drawing Sheets

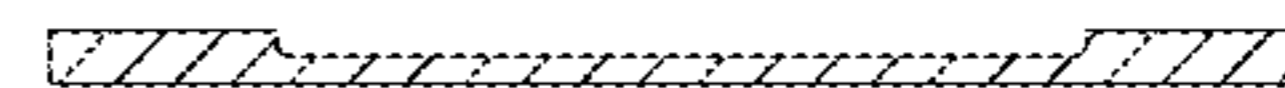
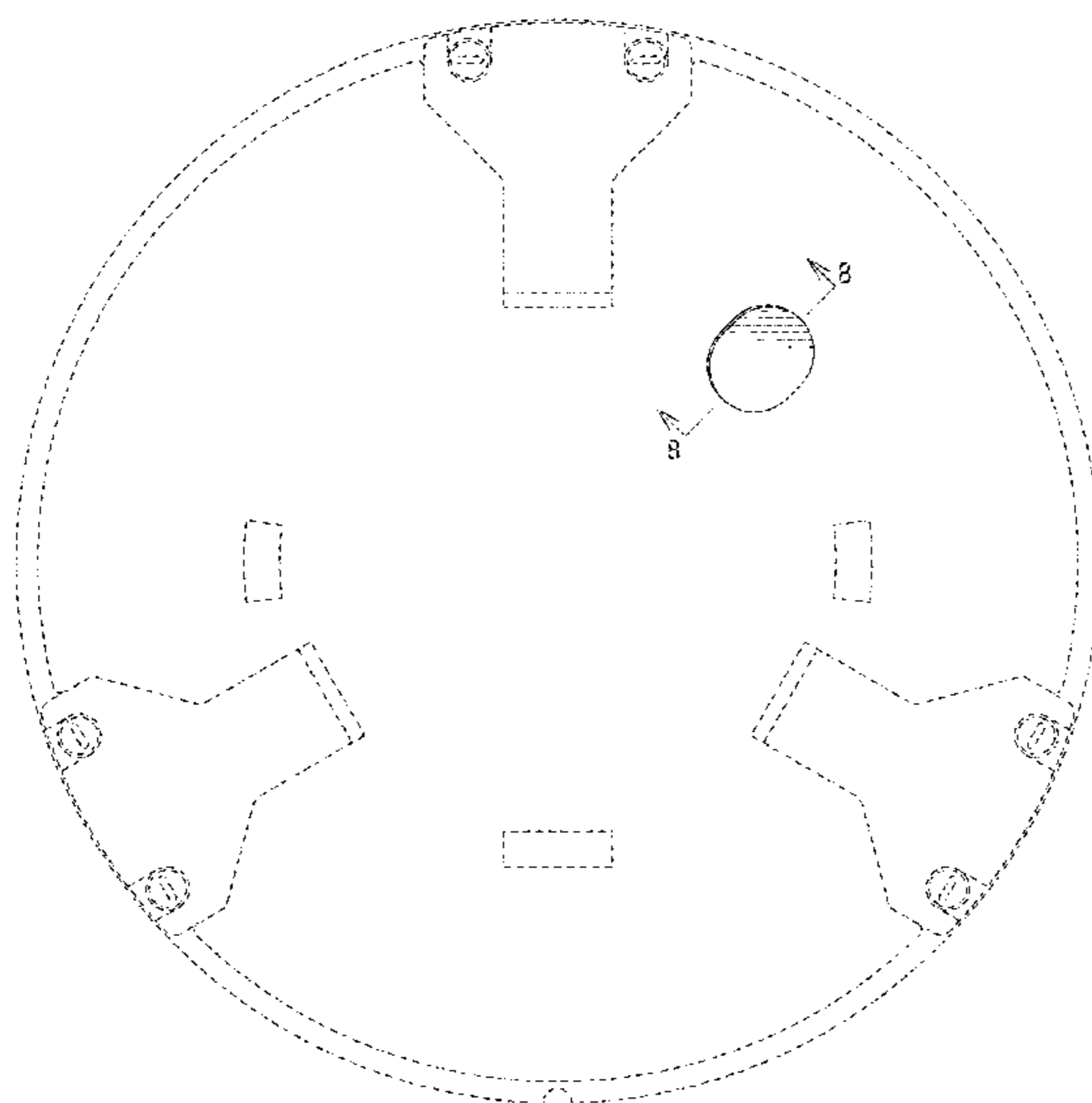


FIG.1

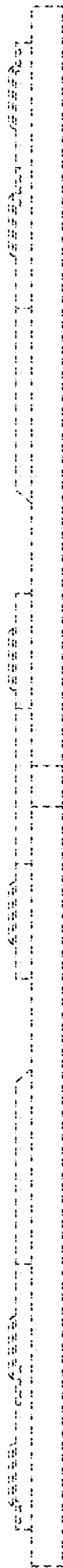


FIG.2

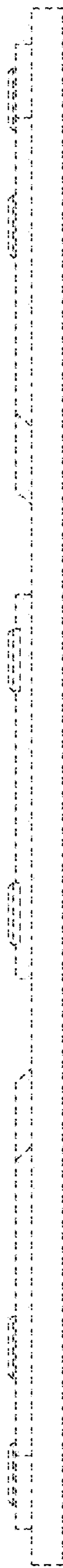


FIG.3

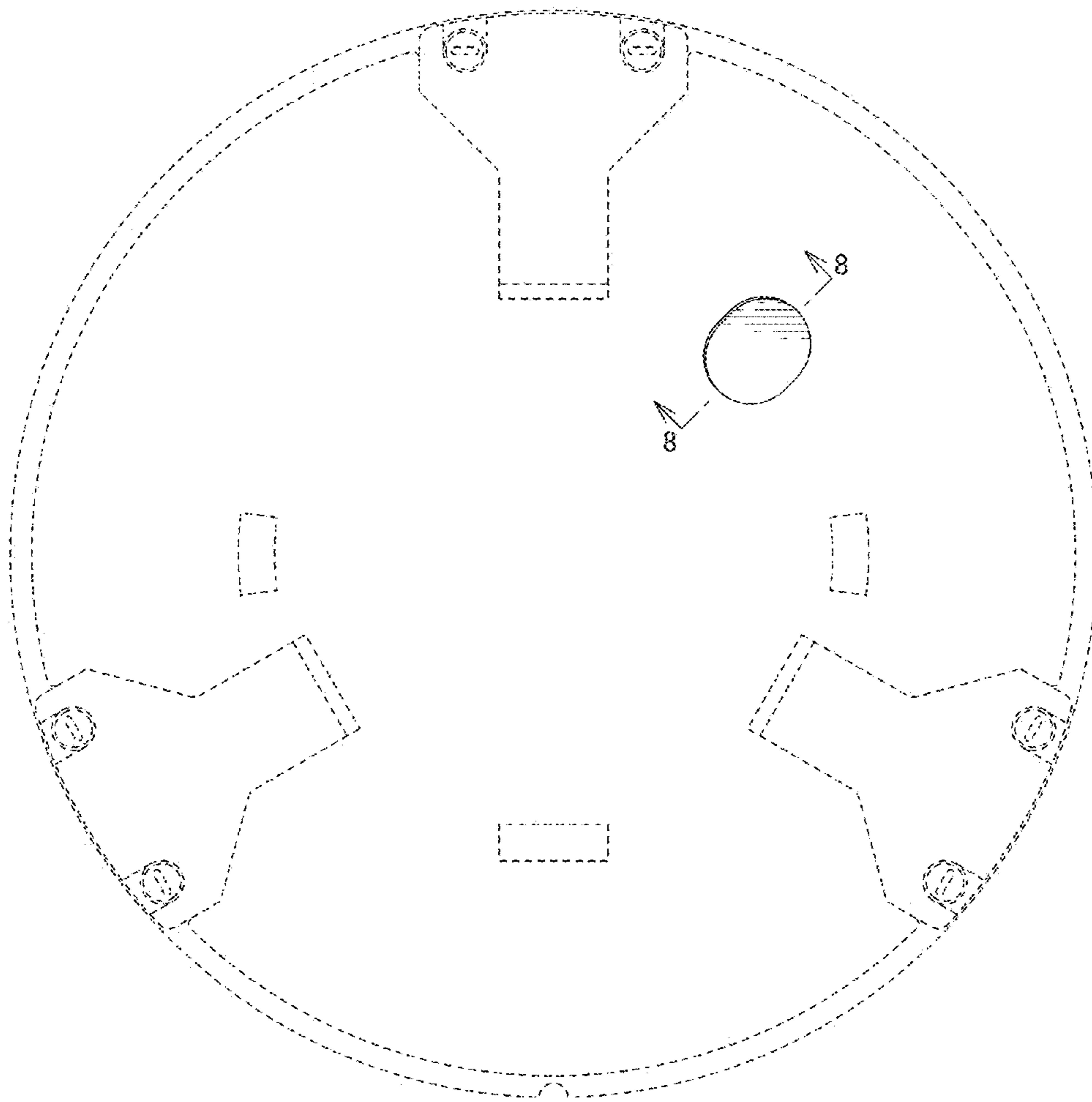
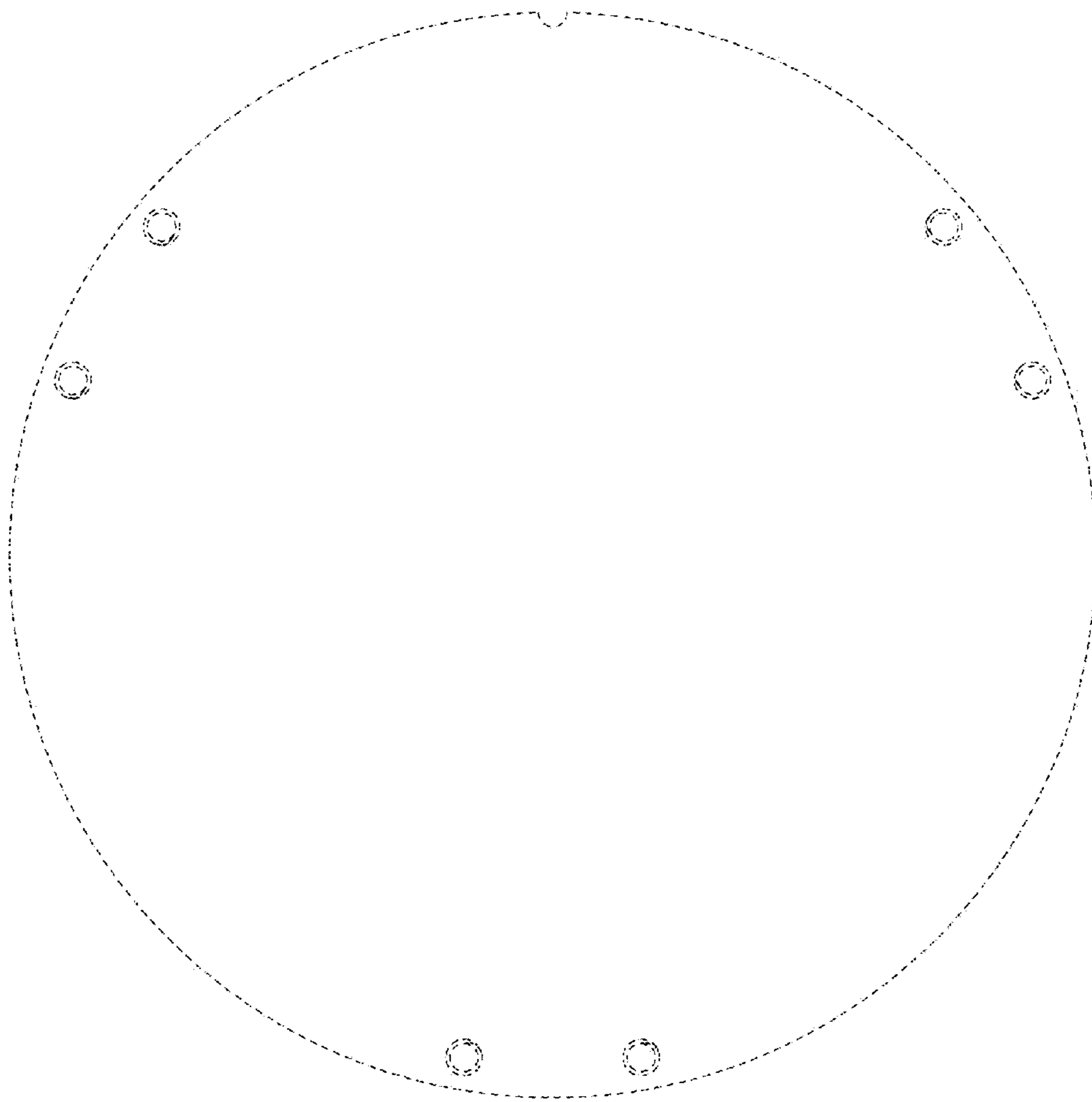


FIG.4



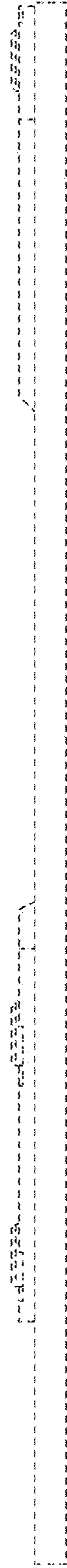


FIG. 5

FIG. 6

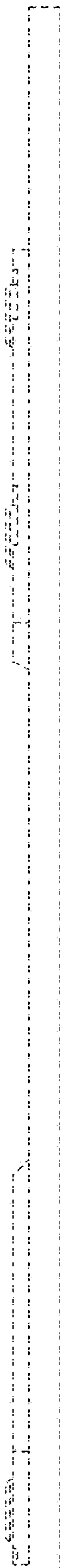


FIG.7

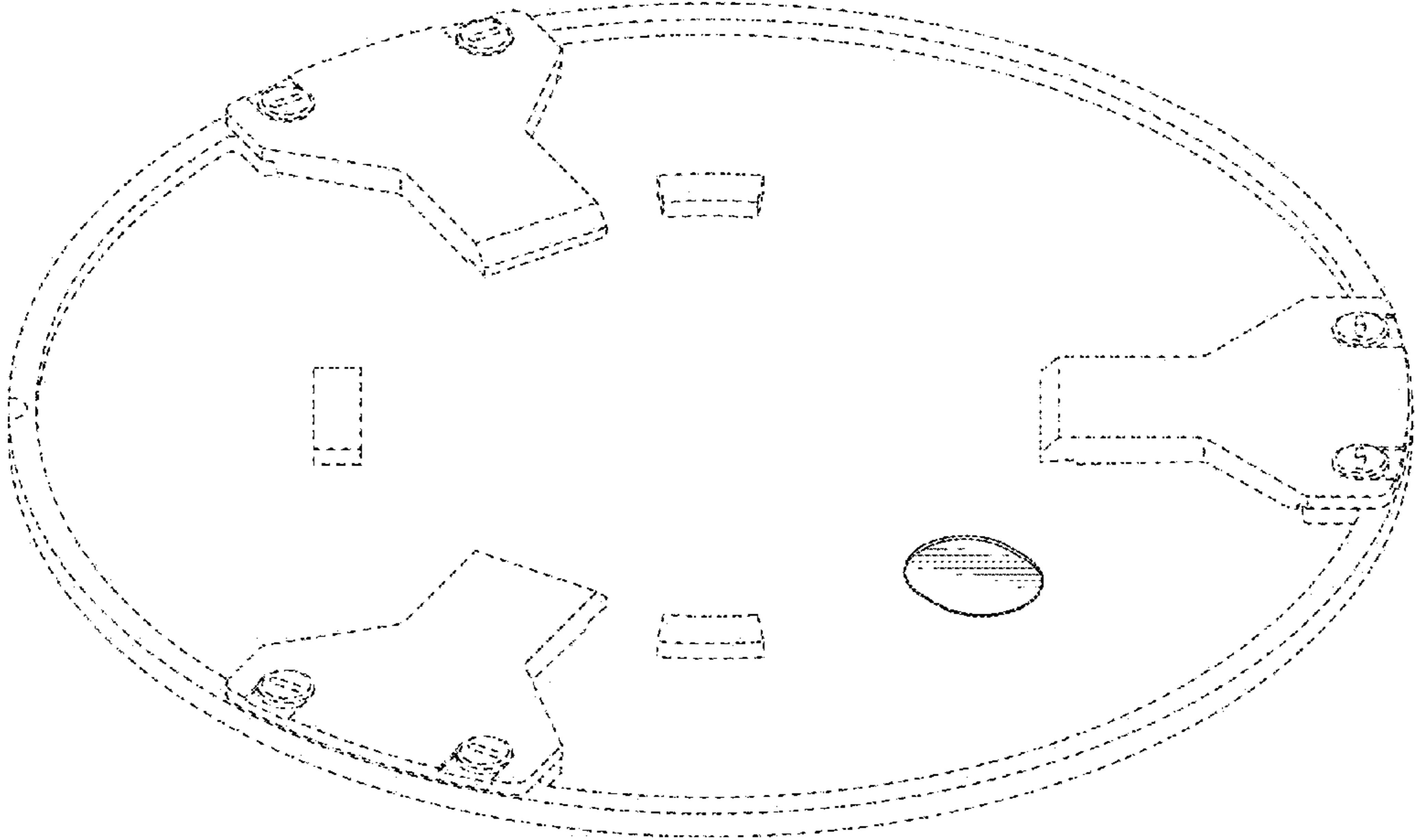


FIG. 8

